IN THE SPECIFICATION:

Please amend the specification as follows:

Please replace the paragraph on page 6, lines 5-11 with the following:

There are various ways in which the fluid handling system 26 can be configured. For example, as shown in Figs. 1A and 1B, a window 16 may be formed in the lower interior region 12b and one or more manifolds may be moveable into place at the window 16 to direct process fluids into the chamber 10. The manifolds and the window 16 are preferably sealed within ~~a containment vessel~~ the fluid handling system 26, a sealed housing that exhausts fumes, gases, etc. that may be released from the manifolds so as to prevent their escape into the surrounding environment.

Please replace the paragraph at page 24, lines 3-5 with the following:

Second embodiment 100 generally includes a process chamber 102, a containment vessel 104, an end effector 106 (see Figure 6), a rotational actuator 108 and a vertical actuator 110.

Please replace the paragraph at page 24, lines 6-12 with the following:

Referring to Fig. 3A, process chamber 102 includes closely spaced chamber walls 111 defining a lower interior region 113a and an upper interior region 113b. An overflow weir 114 is positioned in the lower region 113a, slightly below upper region 113b. Overflow weir 114 includes a wall section 115 over which fluids cascade into the weir 114 during certain processing steps. At the bottom of the chamber 102 is a lower opening 135 ~~(Fig. 3B)~~, and at the top of the chamber is an upper opening 142 (Fig. 4).

Please replace the paragraph at page 24, lines 13-22 with the following:

A vapor/gas manifold 116 is provided for directing vapors/gases into upper region 113b of the chamber. Manifold 116 (best shown in Fig. 4) includes walls 120 on opposite sides of upper region 113b. Vapor/gas ports 122a (see Fig. 4), 122b (see Fig. 5) extend through walls 120 and are fluidly coupled to vapor/gas conduits 124a, 124b. A plurality of orifices 126a, 126b extend from conduits 124a, 124b into the chamber 102. The orifices 126a, 126b may be downwardly angled as shown. The angles are preferably (but are not required to be) within the range of 45° - 80° relative to the normal to walls 120. Each port 122a, 122b is coupled to plumbing that delivers process vapors/gases through the ports 122a,b and into chamber 102 via conduits 124a, b and orifices 126a, 126b.

Please replace the paragraph at page 25, line 26 – page 26 at line 3 with the following:

Figs. 7A through 7E show an alternative end effector 106a having an engaging mechanism found particularly beneficial when used with the described embodiments. An alternative chamber ~~102a~~ having a different shape than the chamber 102 is also described, although various other chamber shapes may be utilized with the end effector 106a. As will be understood from the description that follows, the end effector 106a has two positions relative to the substrate: a transport position in which the substrate is securely held by the end effector, and a process position in which the end effector stabilizes the substrate while permitting process fluids to flow into contact with the substrate's surface.

Please replace the paragraph at page 30, lines 28-31 with the following:

When energized, the transducer 232 creates a zone Z (See Figures 2A-2C) of optimal performance within the process fluid in the chamber. As will be discussed in greater detail below, energization of the zone enhances post-etch quenching, cleaning, rinsing and drying processes through regional boundary layer thinning and microcavitation.